

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

1. (currently amended): A method comprising:
providing a mask which includes:
an array of patterns, each of which corresponds to a display device,
a window disposed between ~~adjacent~~neighboring two of said patterns,
placing a substrate to face said mask;
projecting an incident laser beam onto said substrate through said window of said mask; and
determining a gap between said mask and said substrate in a middle region of said substrate in response to first and second reflected beams, said first reflected beam being generated by said incident laser beam reflected by said mask, and said second reflected beam being generated by said incident laser beam being reflected by said substrate.
2. (original): The method according to claim 1, further comprising:
determining a deflection of said mask based on said determined gap in said middle region.
3. (original): The method according to claim 1, wherein said mask further includes other windows disposed around said array of said patterns, and

wherein said method further comprises:

projecting other incident laser beams onto said substrate through said other windows;

determining gaps between said mask and said substrate near corners of said substrate in response to third and fourth laser beams, said third laser beams being generated by said other incident laser beams being reflected by said mask, and said fourth laser beams being generated by said other incident laser beams being reflected by said substrate, and

determining a deflection of said mask based on said determined gap in said middle region and said gaps near said corners.

4. (original): The method according to claim 1, wherein said patterns are arranged in a row.

5. (original): The method according to claim 1, wherein said patterns are arranged in rows and columns.

6. (original): The method according to claim 1, wherein said substrate is covered with a photo resist, a portion of a main surface of said substrate being exposed, and

said second reflected laser beam is generated by said incident laser beam being reflected by said exposed portion.

7. (currently amended): An proximity exposure method comprising:

providing a mask which includes:

an array of patterns, each of which respectively corresponds to a display device,

a window disposed between ~~adjacent~~neighboring two of said patterns,

placing a substrate on a substrate stage opposed to said mask;

projecting an incident laser beam onto said substrate through said window of said mask; and

determining a gap between said mask and said substrate in a middle region of said substrate in response to first and second reflected beams, said first reflected beam being generated by said incident laser beam reflected by said mask, and said second reflected beam being generated by said incident laser beam being reflected by said substrate; and

removing a deflection of said mask in response to said determined gap in said middle region.

8. (original): The method according to claim 7, further comprising:

projecting other incident laser beams onto said substrate through said other windows;

determining gaps between said mask and said substrate near corners of said substrate in response to third and fourth laser beams, said third laser beams being generated by said other incident laser beams being reflected by said mask, and said fourth laser beams being generated by said other incident laser beams being reflected by said substrate, and

determining said deflection of said mask based on said determined gap in said middle region and said gaps near said corners.

9. (original): The method according to claim 7, wherein said removing includes:
securing said mask and a glass plate to form a sealed space between said mask and said glass plate; and
inflating or evacuating said sealed space in response to said determined deflection.

10. (original): The method according to claim 7, wherein said determining said gap in said middle region is executed every time said substrate is exchanged.

11. (original): The method according to claim 7, wherein said determining said gap in said middle region is executed every time said mask is exchanged.